



162162



G00002

A B S T R A C T

According to one embodiment, a photomask blank
wherein a second film (14) is stacked on a first film
(13), the first film containing chromium and which is
5 not substantially etched by the dry etching using
fluorine and which is etchable by the dry etching using
oxygen-containing chlorine, and the second film
containing no chromium and which is etchable by dry
etching using fluorine and dry etching using oxygen-
10 containing chlorine.